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27. The method of claim 1 wherein the resin is treated with a lactate.

28. The method of claim 1 wherein the resin is treated with a hydroxy-containing solvent.

~~29.~~ 28. The method of claim 1 wherein the resin is treated with an alkane solvent.

~~30.~~ 29. A method for preparation of a photoresist composition comprising:
(a) washing a prepared resin with one or more organic solvents, the resin comprising phenolic and alkyl acrylate photoacid labile groups;
(b) admixing the treated resin with a photoactive component to provide a photoresist composition.

~~31.~~ 30. The method of claim ~~29~~ 29 wherein the resin is washed with methylene chloride.

~~32.~~ 31. The method of claim ~~29~~ 29 wherein the resin is washed with a halogenated solvent.

~~33.~~ 32. The method of claim ~~29~~ 29 wherein the resin is washed with a solvent having an ester.

~~34.~~ 33. The method of claim ~~29~~ 29 wherein the resin is washed with a lactate.

~~35.~~ 34. The method of claim ~~29~~ 29 wherein the resin is treated with a hydroxy-containing solvent.

~~36.~~ 35. The method of claim ~~29~~ 29 wherein the resin is treated with an alkane solvent.

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36. A photoresist composition comprising a photoactive component and a resin comprising phenolic and alkyl acrylate photoacid labile groups, the resin obtainable washing a prepared resin with one or more organic solvents.

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37. The photoresist of claim 36 wherein the resin is washed with methylene chloride.

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38. The photoresist of claim 36 wherein the resin is washed with a halogenated solvent.

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39. The photoresist of claim 36 wherein the resin is washed with a solvent having an ester.

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40. The photoresist of claim 36 wherein the resin is washed with a lactate.

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41. The photoresist of claim 36 wherein the resin is treated with a hydroxy-containing solvent.

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42. The photoresist of claim 36 wherein the resin is treated with an alkane solvent.

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43. A substrate having coated thereon a photoresist of claim 36.

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44. The substrate of claim 43 wherein the photoresist composition is coated on a microelectronic wafer substrate.

REMARKS

Claim 1 has been amended, claims 13, 14 and 16-24 have been cancelled without prejudice, and claims 25-44 have been added. No new matter has been added by virtue of the